

Figure 1: (a) Schematic of the spatial ALD tool used to deposit films in LHAR structures schematically shown in (b). The membrane functions as sidewall of the trench and is removed after deposition to analyze the deposited film.

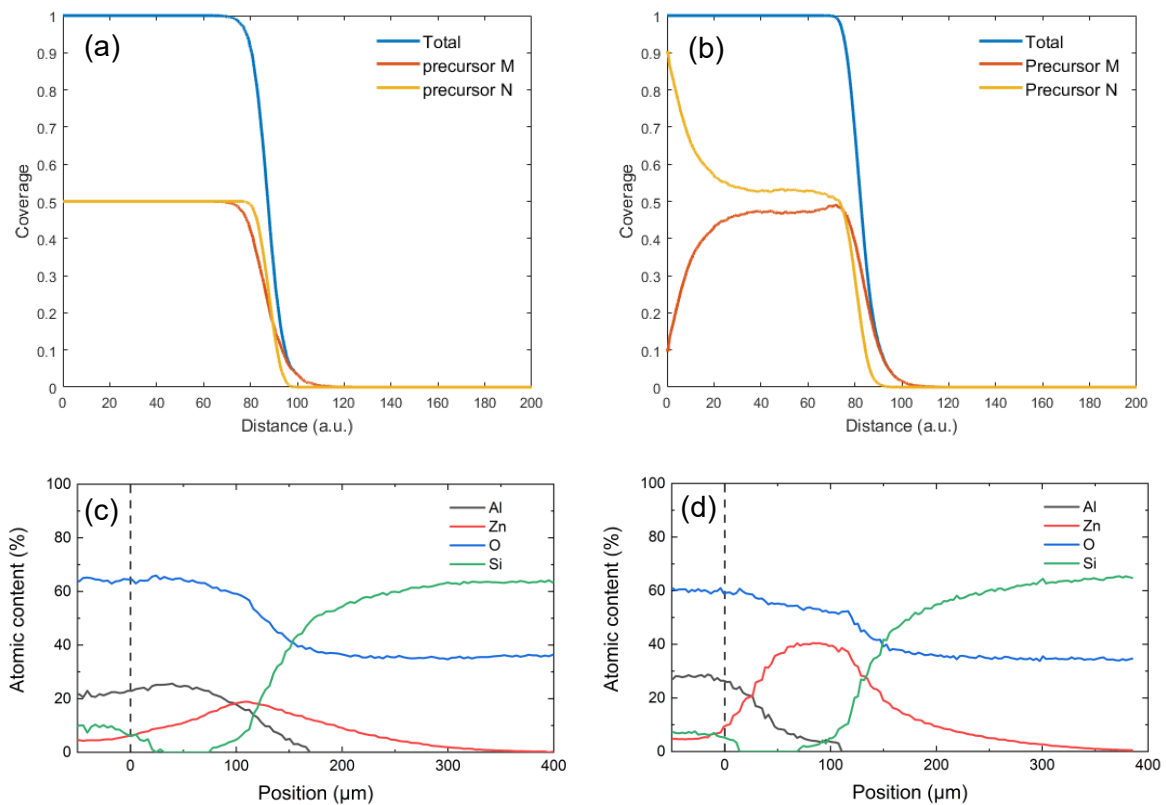


Figure 2: Typical simulated coverage profiles inside a trench of ternary oxide obtained from Monte Carlo simulations (a,b) and of AlZnO obtained from XPS (c,d). Profiles result from the supercycle method (a,c) and the co-injection method (b,d). In the model, equal precursor dose was used for two metal precursors with different sticking probabilities.